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PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

INVENTOR: C. Obszarny ) EXAMINER: P. Kim  
SERIAL NO.: 09/116,395 ) ART UNIT: 2851  
FILING DATE: 16 July 1998 ) DATE: 19 June 2000

FOR: APPARATUS AND METHOD FOR IN-SITU ADJUSTMENT OF  
LIGHT TRANSMISSION IN A PHOTOLITHOGRAPHY  
PROCESS

**AMENDMENT**

Assistant Commissioner of Patents  
Washington, DC 20231

Dear Sir:

Responsive to the Office Action mailed 20 March 2000, please amend the application  
as follows:

**In the Claims**

Please amend claims 1, 3, 7, 17 and 18 as follows:

- 1 1. (twice amended) An apparatus for varying optical transmission intensity on a substrate  
2 wafer in a photolithography process comprising:  
3     a first polarizer capable of adjustment during optical transmission such that an optical  
4         image focused on said substrate wafer is varied in contrast, said adjustment made  
5         relative to a second polarizer; and,  
6     a photo mask patterned with a plurality of optically transparent and optically opaque  
7         regions, wherein said transparent regions are impregnated with said second  
8         polarizer[,] fixed in a predetermined direction, and said opaque regions comprise a

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